



Conference Background

The EIPBN Conference is dedicated to lithographic patterning science, nanomanufacturing process technology, and the applications these methods enable. For 58 years, the conference has brought together engineers and scientists from industries and universities from all over the world to report on and discuss recent progress and future trends.

Meeting Format

The conference opens on Tuesday afternoon with a special commercial session which features vendors of materials and equipment relevant to the conference. Plenary sessions will be included. The main oral portion of the conference is organized in three parallel sessions. The planned length of presentation and discussion is 30 minutes for invited papers and 20 minutes for contributed papers.

A key feature of the technical program is the poster session that includes invited and contributed papers. There is only one poster session, but posters will be displayed for informal viewing throughout the entire conference.

Technical Scope

Abstracts representing high quality original research are invited in the topics of nanopatterning and fabrication. Example topic areas include:

- Nanoimprint lithography
- Directed Self-Assembly
- Biologically-inspired Assembly
- Atomic and Molecular manipulation
- Electron- and ion-beam lithography
- Advanced optical lithography
- Dimensional metrology, alignment
- Imaging methods
- Scanned-probe-based patterning
- Resists and resist processing
- Maskless lithography
- Soft lithography and embossing
- Extreme UV lithography
- Nanoscale processing techniques

Topics related to fabrication and patterning for emerging technologies include:

- Simulation and modeling for the nano-scale
- Integrated nano-photonics
- Patterned media and data storage
- Nano-electronics
- Nano-biology
- Micro- and nano-scale MEMS
- Micro- and nano-fluidics
- Nanofabrication for energy sources

Conference Registration

We strongly encourage you to register on line by using our website www.eipbn.org. Early registration and special student rates are available. The early registration deadline is May 12, 2014.

Conference Location

The conference will be held at the Omni Shoreham Hotel in Washington, DC. The four-diamond Omni Shoreham Hotel is situated on 11 lush acres just steps away from the National Zoo and the DC Metro. Located in picturesque Rock Creek, this elegant urban retreat boasts a resort atmosphere. Since 1930, the luxurious Omni Shoreham Hotel in Washington, DC has played host to presidents, world leaders and inaugural balls, making it a true Washington landmark.

Omni Shoreham Hotel
2500 Calvert Street NW
Washington, District of Columbia 20008
Phone: (202) 234-0700
Fax: (202) 265-7972
<http://www.omnihotels.com/FindAHotel/WashingtonDCShoreham.aspx>

On-line hotel registration will be available on the EIPBN website

Abstract Submission

Abstracts should be submitted online at

www.eipbn.org

Abstracts are limited to one page of text (12 point or larger type) and a second, optional page with up to four figures.

Abstract deadline: January 11, 2014

Late submissions may be considered but only if they report truly outstanding results. Please prepare abstracts carefully and describe accomplishments specifically. Authors will be notified of acceptance by April 11, 2014.

Micrograph Contest

On a more cultural level, EIPBN offers the opportunity to immortalize your favorite micrograph(s). Categories and previous winners are described on our website.

Manuscript Submission

Manuscripts must be submitted around the time of the conference and will be subjected to a critical peer review before they can be accepted for publication in the Nov/Dec 2014 issue of the Journal of Vacuum Science and Technology. Please note that authors who are not members of the American Vacuum Society may be required to pay a per page publication charge.

Student Support

Limited funds are available to support student travel. The Conference Chair must receive a letter requesting support from the student's advisor by May 1, 2014. For helping with housing costs a "Room with another student" option may be available at the Omni.

Conference Chair

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To add your name to the mailing list, please
mail a business card or e-mail to the
Conference Chair.

Other Information

The EIPBN conference is incorporated as a nonprofit organization in the state of New Jersey and is co-sponsored by the American Vacuum Society (www.avs.org), in cooperation with the IEEE Electron Devices, Lasers and Electro-optics Societies and the Optical Society of America. It is organized by a steering committee that elects two new members each year from regular attendees of the conference.

Call for Papers



**The 58th International Conference
on Electron, Ion, and Photon Beam
Technology, and Nanofabrication**

May 27 – 30, 2014

www.eipbn.org

Omni Shoreham Hotel

